

ABSTRACT

SUBSTRATE PROCESSING GAS, STORAGE CONTAINER, AND SUBSTRATE
PROCESSING METHOD

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A substrate processing gas of the present invention contains IF₅; and IF₇, in which a content of the IF₅ is equal to or more than 1 ppm and equal to or less than 2% on a volume basis with respect to a total amount of the IF₅ and the IF₇.

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[No figure]